

SUPPLEMENTARY MATERIAL

THERMODYNAMIC ANALYSIS OF TRISILOXANE SURFACTANT ADSORPTION AND AGGREGATION PROCESSES

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Fig. S1. A plot of mole fraction of the area occupied by TS-OE12 at the water-air interface (X_s) vs. the logarithm of its concentration ($\log C_s$) at a temperature equal to 293 K, 303 K and 313 K determined from Eq. (4).

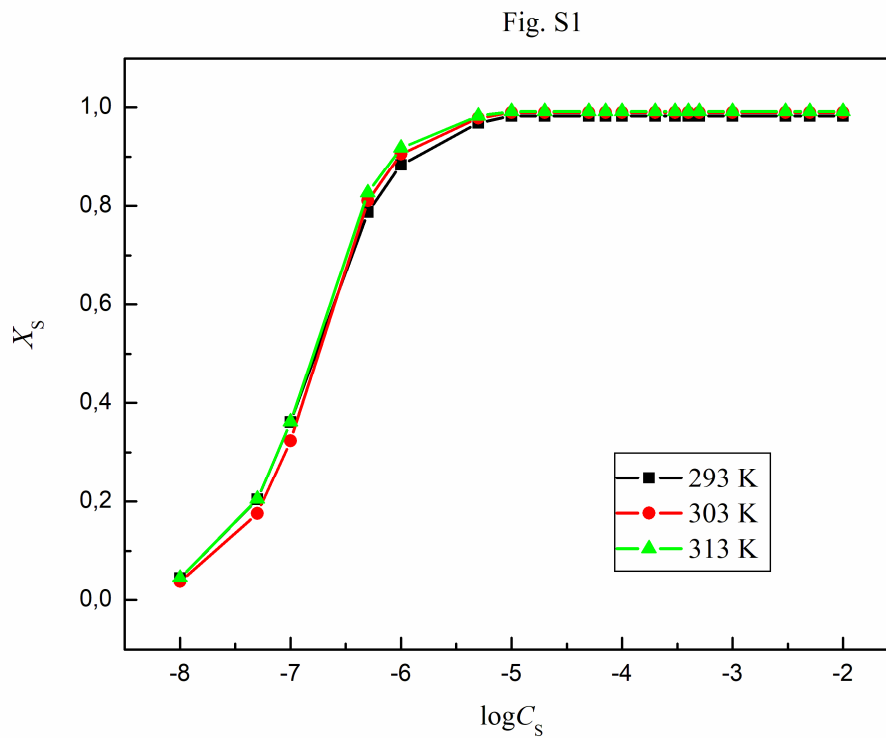


Fig. S2. A plot of mole fraction of the area occupied by TS-OE12 at the water-air interface (X_s) vs. the logarithm of its concentration ($\log C_s$) at a temperature equal to 293 K, 303 K and 313 K determined from Eq. (6).

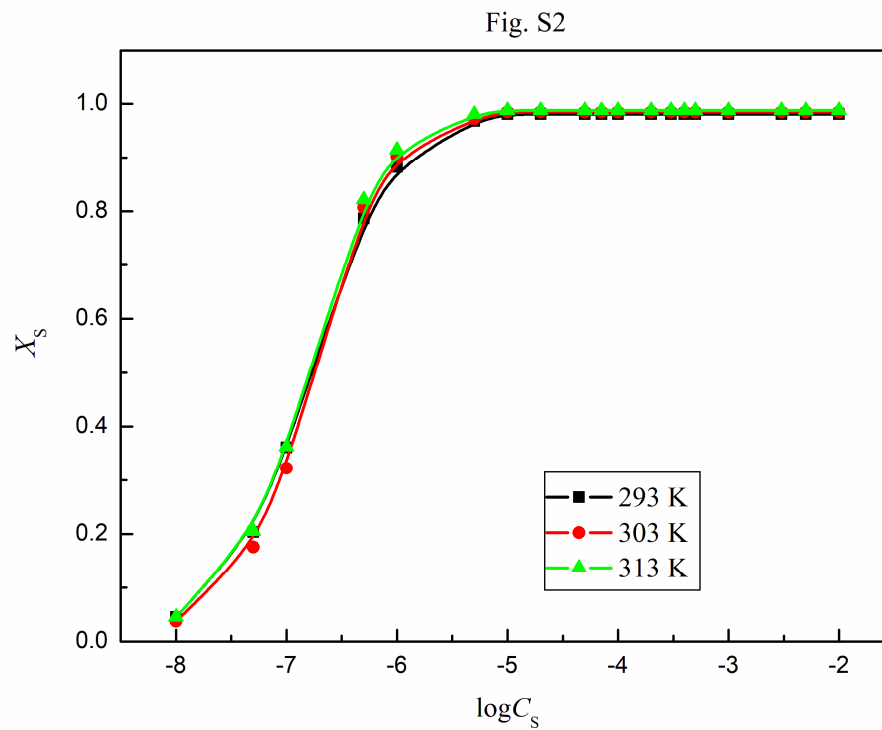


Fig. S3. A plot of logarithm of mole fraction of the area occupied by TS-OE12 at the water-air interface (X_s) vs. the logarithm of its concentration ($\log C_s$) at a temperature equal to 293 K, 303 K and 313 K determined from Eq. (6).

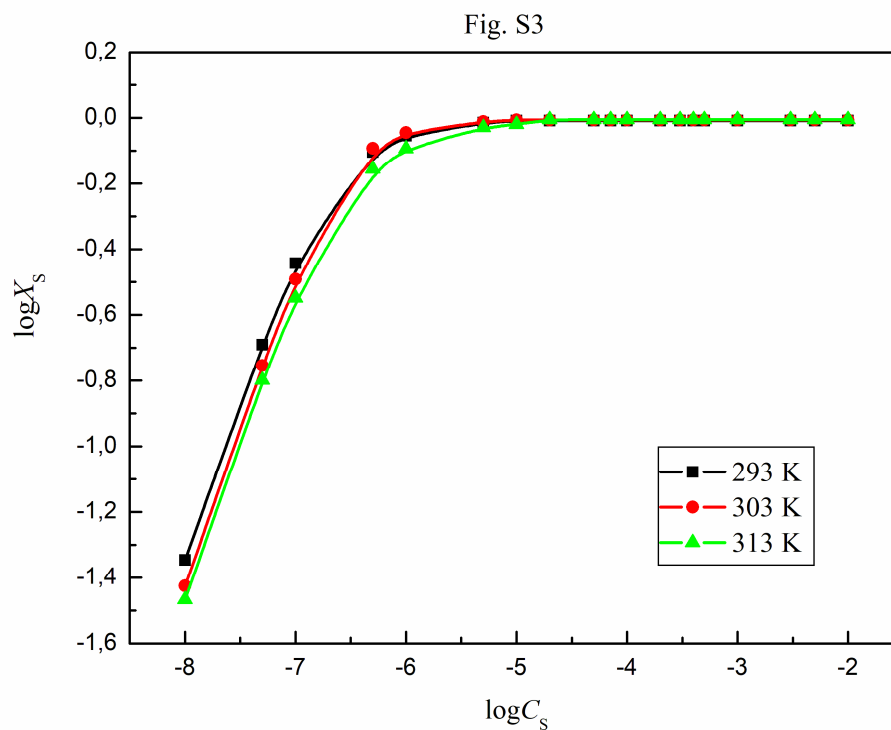


Fig. S4 Values of surface tension (γ_{LV}) of aqueous solutions of TS-OE12 (curves 1–3) determined from Eq. (7) at 298 K, 303 K and 313 K vs. the logarithm of surfactant concentration ($\log C_s$).

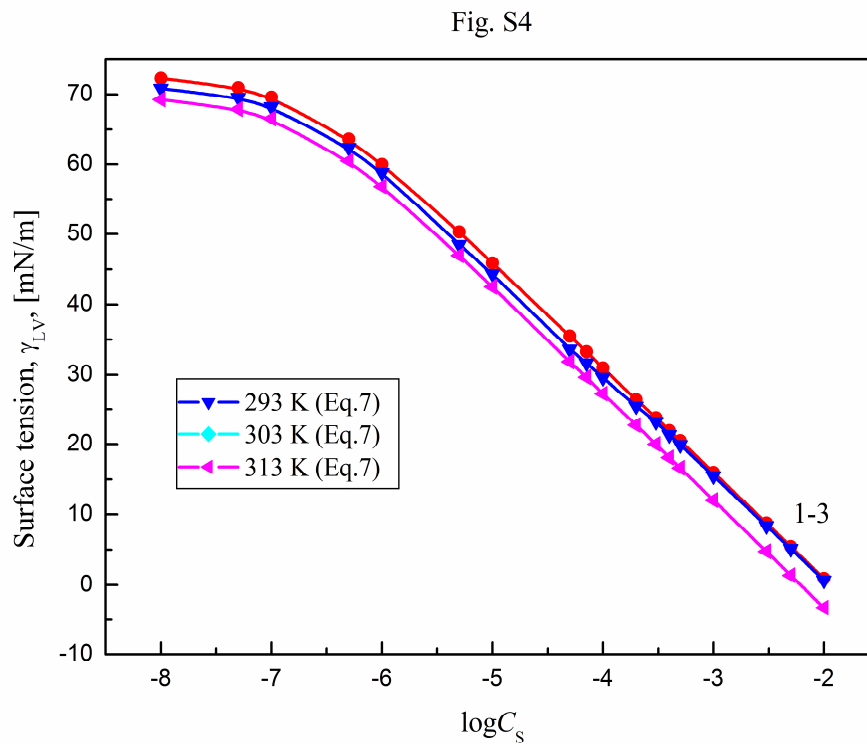


Fig. S5 A plot of the pyrene I_1/I_3 and I_3/I_1 ratios vs. the logarithm of TS-OE12 concentration ($\log C_s$) at 303 K.

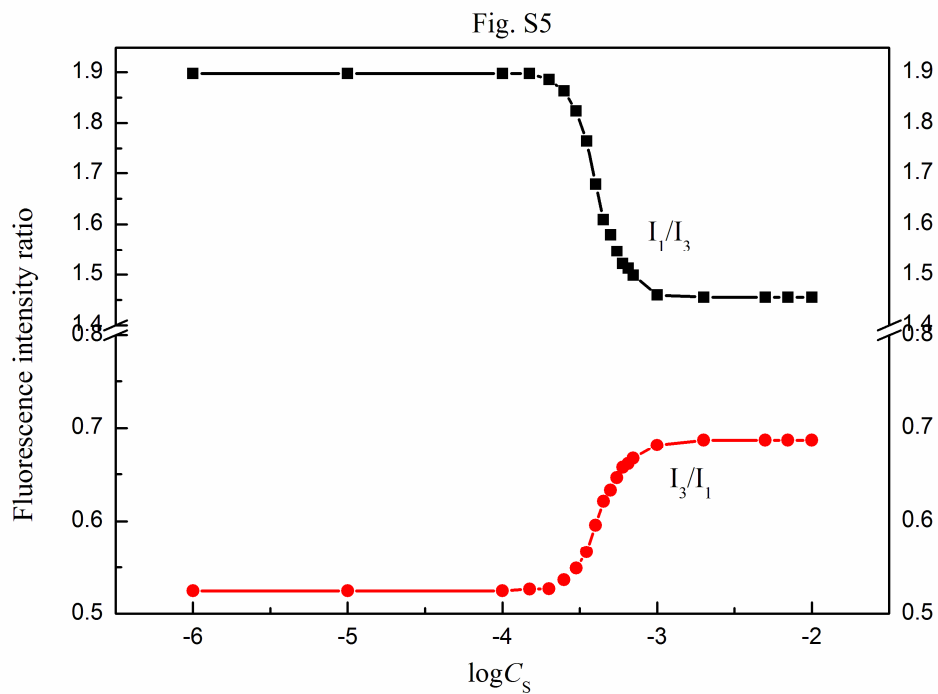


Fig. S6 A plot of the pyrene I_1/I_3 and I_3/I_1 ratios vs. the logarithm of TS-OE12 concentration ($\log C_s$) at 313 K.

